

L Number	Hits	Search Text	DB	Time stamp
1	1	MEM and RF and (hard adj mask) and (patterned adj resistor) ("6100477").PN.	USPAT	2004/05/01 14:58
2	1		USPAT	2004/05/01 15:15
3	1	(("6100477").PN.) and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning)	USPAT	2004/05/01 15:16
4	1	("5619061").PN.	USPAT	2004/05/01 15:16
5	1	((("6100477").PN.) and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning)) and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning))	USPAT	2004/05/01 15:18
6	1	("6645821").PN.	USPAT	2004/05/01 15:18
7	1	((("6645821").PN.) and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning))	USPAT	2004/05/01 15:24
8	1	("6326256").PN.	USPAT	2004/05/01 15:24
9	1	((("6326256").PN.) and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning))	USPAT	2004/05/01 15:29
10	1	("5356826").PN.	USPAT	2004/05/01 15:29
11	1	((("5356826").PN.) and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning)) and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning))	USPAT	2004/05/01 15:31
12	1	("5547896").PN.	USPAT	2004/05/01 15:31
13	1	((("5547896").PN.) and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning))	USPAT	2004/05/01 15:59
14	1		USPAT	2004/05/01 15:35
15	1		USPAT	2004/05/01 15:35
16	1		USPAT	2004/05/01 15:36
17	1		USPAT	2004/05/01 15:38
18	1		USPAT	2004/05/01 15:38
19	1		USPAT	2004/05/01 15:39
20	1		USPAT	2004/05/01 15:39
21	1	("5603847").PN.	USPAT	2004/05/01 15:40
22	1	((("5603847").PN.) and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning))	USPAT	2004/05/01 15:41

23	1	"5420063".PN. and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning)	USPAT	2004/05/01 15:45
24	1	"5407841".PN. and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning)	USPAT	2004/05/01 15:45
25	203	438/329	USPAT	2004/05/01 15:59
26	178	438/330	USPAT	2004/05/01 15:59
27	1918	438/238	USPAT	2004/05/01 15:59
28	1059	438/381	USPAT	2004/05/01 15:59
29	390	438/382	USPAT	2004/05/01 15:59
30	486	438/384	USPAT	2004/05/01 16:01
31	324	438/385	USPAT	2004/05/01 16:01
32	502	438/704	USPAT	2004/05/01 16:01
33	1461	438/706	USPAT	2004/05/01 16:01
34	1277	438/745	USPAT	2004/05/01 16:01
-	1	09/941031	USPAT	2004/04/30 16:08
-	1	("6698082").PN.	USPAT	2004/04/30 16:09
-	1	("5619061").PN.	USPAT	2004/04/30 16:11
-	1		USPAT	2004/04/30 16:09
-	1		USPAT	2004/04/30 16:09
-	1	(patterned adj resistor adj length) and uniform and material and resistor and hard and mask and electrode and stack and etch	USPAT	2004/04/30 16:14
-	1	(patterned adj resistor adj length) and uniform	USPAT	2004/04/30 16:13
-	1	(patterned adj resistor adj length)	USPAT	2004/04/30 16:14
-	1	(resistor adj length) and uniform and material and resistor and hard and mask and electrode and stack and etch	USPAT	2004/04/30 16:17
-	1		USPAT	2004/04/30 16:20
-	1		USPAT	2004/04/30 16:15
-	1		USPAT	2004/04/30 16:15
-	1		USPAT	2004/04/30 16:15
-	1		USPAT	2004/04/30 16:16
-	1		USPAT	2004/04/30 16:17
-	1		USPAT	2004/04/30 16:17
-	1		USPAT	2004/04/30 16:17
-	1		USPAT	2004/04/30 16:17
-	1		USPAT	2004/04/30 16:29
-	1	"6376787".PN. and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning)	USPAT	2004/05/01 15:17
-	1	(("6698082").PN.) and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning)	USPAT	2004/04/30 16:27
-	1		USPAT	2004/04/30 16:28
-	1		USPAT	2004/04/30 16:28
-	1	"5603847".PN. and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning)	USPAT	2004/05/01 15:15

-		1	"5356826".PN. and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning)	USPAT	2004/04/30 16:47
-		745	MEM and switch and RF	USPAT	2004/04/30 16:48
-		73	MEM and switch and RF and uniform and resistor and material	USPAT	2004/04/30 16:49
-		9	MEM and switch and RF and uniform and resistor and material and hard and mask and metal and electrode and length	USPAT	2004/05/01 14:57
-		9	(MEM and switch and RF and uniform and resistor and material and hard and mask and metal and electrode and length) and (metal or resistor or paatern or patterned or etch or etching or patterning or length or hard or mask or uniform or stack or electrode or bottom or lower or micro or electromechanical or anchor or RF or radio or wet or etch or etching or patterning)	USPAT	2004/04/30 17:35
-		3	09/452691	USPAT	2004/04/30 17:35

5/1/04